**BM 300** 

## AIXTRON



# 300 mm Wafer-scale Production of Carbon Nanotubes and Graphene

#### **Features**

- 1050° C substrate heater
- Uniform gas delivery through showerhead
- Precise precursor concentration control
- Heater to showerhead gap adjust
- Wafer rotation during process
- ARGUS real-time wafer temperature mapping
- Optical ports at normal incidence to wafer





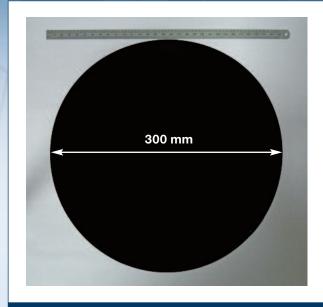
**BM 300 Process Module and Handler System** 

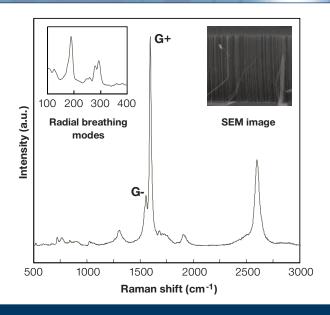
### **BM 300**



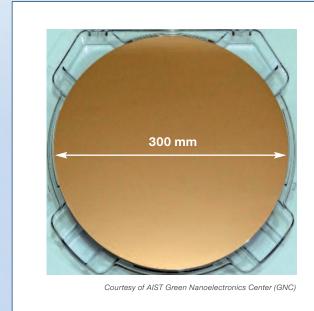


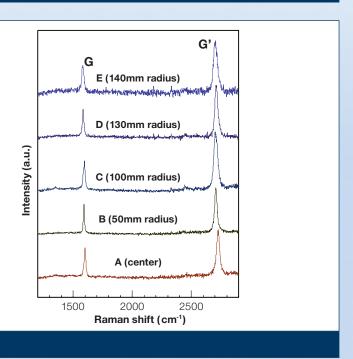
### Results





**High Quality Carbon Nanotubes** 





**High Quality Graphene**